Special Issue

Plasma Physics: Theory, Methods and Applications

Message from the Guest Editor

This Special Issue related to plasma physics is focused on the theory, method, and application of plasma. Therefore, we welcome the submission of any type of works that report on the generation of laboratory plasma, the investigation of its property by means of numerical simulation and experimental diagnostics, and the application of plasma, including both low-temperature and high-temperature plasmas. Moreover, this Special Issue is also suited for the submission of works that attempt to build relations between laboratory plasma and astrophysics plasma. Keywords

- low-temperature plasma
- thermal nuclear fusion plasma
- film deposition and etching process
- numerical simulation and experimental diagnostic
- astrophysics plasma
- thermal and chemical equilibrium

Guest Editor

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Message from the Editor-in-Chief

As the world of science becomes ever more specialized, researchers may lose themselves in the deep forest of the ever increasing number of subfields being created. This open access journal Applied Sciences has been started to link these subfields, so researchers can cut through the forest and see the surrounding, or quite distant fields and subfields to help develop his/her own research even further with the aid of this multi-dimensional network.

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